

## PHOTORESIST COMPOSITIONS COMPRISING POLYCYCLIC POLYMERS WITH ACID LABILE PENDANT GROUPS

**Publication number:** JP2001516780 (T)

**Publication date:** 2001-10-02

**Inventor(s):**

**Applicant(s):**

**Classification:**

- international: C08F232/00; C08G61/08; G03F7/023; G03F7/039;  
C08F232/00; C08G61/00; G03F7/023; G03F7/039; (IPC1-  
7): C08G61/08; G03F7/039

- European: C08G61/08; G03F7/039

**Application number:** JP20000511803T 19980903

**Priority number(s):** US19970928573 19970912; WO1998US18408 19980903

**Also published as:**

WO9914256 (A1)

WO9914256 (A8)

CN1269810 (A)

CN1148396 (C)

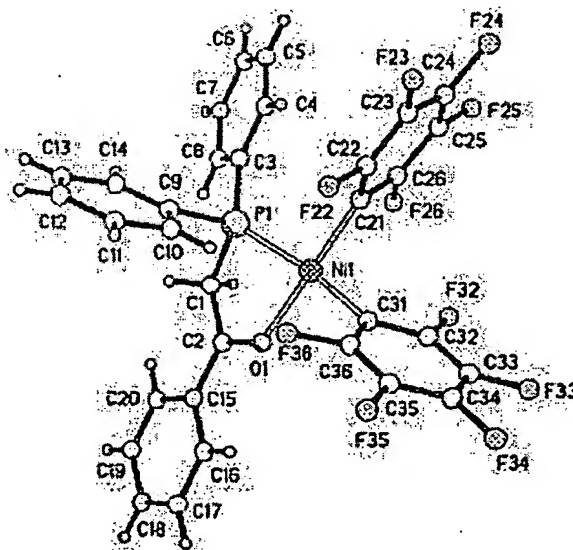
AU748214 (B2)

more >>

Abstract not available for JP 2001516780 (T)

Abstract of corresponding document: **WO 9914256 (A1)**

The present invention relates to a radiation sensitive photoresist composition comprising a photoacid initiator and a polycyclic polymer comprising repeating units that contain pendant acid labile groups. Upon exposure to an imaging radiation source the photoacid initiator generates an acid which cleaves the pendant acid labile groups effecting a polarity change in the polymer. The polymer is rendered soluble in an aqueous base in the areas exposed to the imaging source.



Data supplied from the esp@cenet database — Worldwide

# PHOTORESIST COMPOSITIONS COMPRISING POLYCYCLIC POLYMERS WITH ACID LABILE PENDANT GROUPS

**Publication number:** WO9914256 (A1)

**Publication date:** 1999-03-25

**Inventor(s):** RHODES LARRY F; BELL ANDREW; JAYARAMAN SAIKUMAR; LIPIAN JOHN-HENRY; GOODALL BRIAN L; SHICK ROBERT A

**Applicant(s):** GOODRICH CO B F [US]

**Classification:**

- international: C08F232/00; C08G61/08; G03F7/023; G03F7/039; C08F232/00; C08G61/00; G03F7/023; G03F7/039; (IPC1-7): C08G61/08; G03F7/023

- European: C08G61/08; G03F7/039

**Application number:** WO1998US18408 19980903

**Priority number(s):** US19970928573 19970912

**Also published as:**

WO9914256 (A8)  
CN1269810 (A)  
CN1148396 (C)  
AU748214 (B2)  
AU9376698 (A)

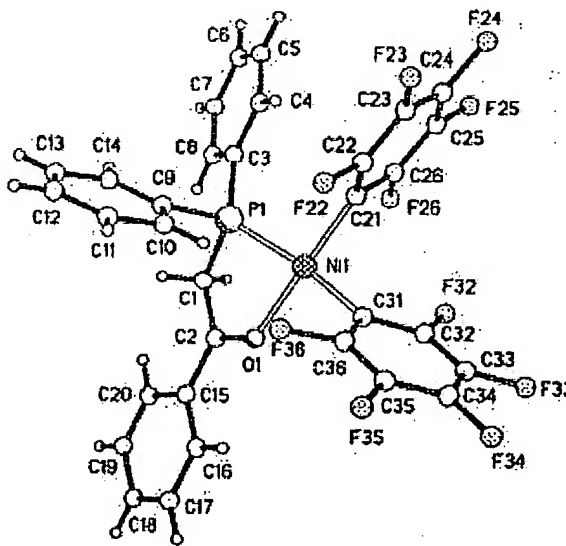
more >>

**Cited documents:**

EP0789278 (A2)  
WO9720871 (A2)  
WO9733198 (A1)

## Abstract of WO 9914256 (A1)

The present invention relates to a radiation sensitive photoresist composition comprising a photoacid initiator and a polycyclic polymer comprising repeating units that contain pendant acid labile groups. Upon exposure to an imaging radiation source the photoacid initiator generates an acid which cleaves the pendant acid labile groups effecting a polarity change in the polymer. The polymer is rendered soluble in an aqueous base in the areas exposed to the imaging source.



Data supplied from the esp@cenet database — Worldwide